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U.S. Patent and Trademark Office  <b>INFORMATION DISCLOSURE STATEMENT</b>  (Use several sheets if necessary)	Attorney Docket No.: UMC-96-279	Serial No.: <del>Not Assigned</del> <del>08/458,460</del> 09/546,174
	Applicants: Chih-Chien Liu, et al.	
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**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Sub-Class	Filing Date if Appropriate

**FOREIGN PATENT DOCUMENTS**

Document Number	Date	Country	Class	Sub-Class	Translation Yes/No

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)**

RS	J.T. Pye, et al., "High-Density Plasma CVD and CMP for 0.25- $\mu$ m Intermetal Dielectric Processing," Solid State Technology, December 1995, pp.65-69.

EXAMINER <i>Rabon Bryant</i>	DATE CONSIDERED 8/1/99 1/15/01
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.